

Plan Apochromat Objectives

Extra And Ultra Long Working Distance



Extra Long Working Distance Objectives

PARFOCALITY ADJUSTABLE

PLAN APO ELWD PA

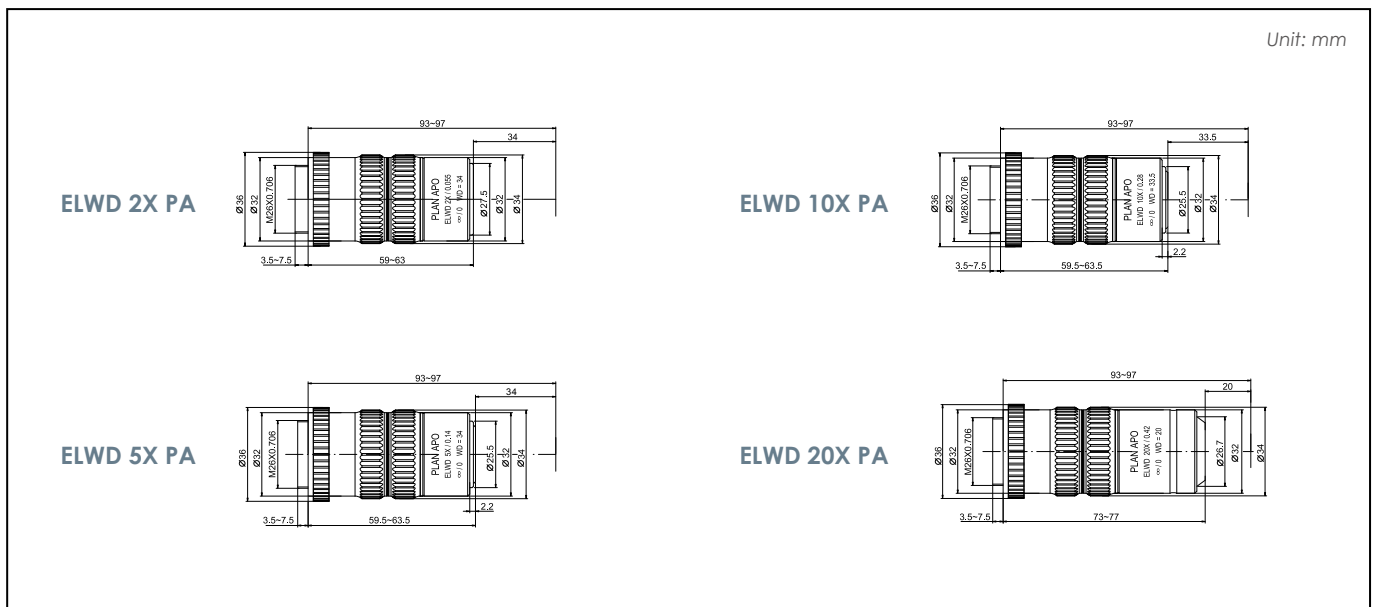
- The unique Motic feature of parfocality adjustability assures smooth transitions between magnifications as a convenient time saving function.
- The infinity corrected and strain-free optical system provides crisp and high contrast images at the numerical apertures and working distance demanded.



ELWD 20X PA

Parfocality Adjustable Objective

Schematic Diagrams of Plan Apochromat ELWD Objectives PA [Parfocality Adjustable]



Specifications Chart

Plan Apochromat ELWD Objectives PA [Parfocality Adjustable]

Mag.	N.A	W.D (mm)	F (mm)	R (µm)	D.F (µm)	FOV (mm) (Ø24 eyepiece)	FOV (VxH,mm) (1/2" chip sensor)	FOV (VxH,mm) (2/3" chip sensor)	Weight (g)
ELWD 2X PA	0.055	34.0	100	5.0	91	Ø 12	2.4x3.2	3.3x4.4	270
ELWD 5X PA	0.140	34.0	40	2.0	14	Ø 4.8	0.96x1.28	1.32x1.76	260
ELWD 10X PA	0.280	33.5	20	1.0	3.5	Ø 2.4	0.48x0.64	0.66x0.88	270
ELWD 20X PA	0.420	20.0	10	0.7	1.6	Ø 1.2	0.24x0.32	0.33x0.44	320

Extra Long Working Distance Objectives

PLAN APO ELWD

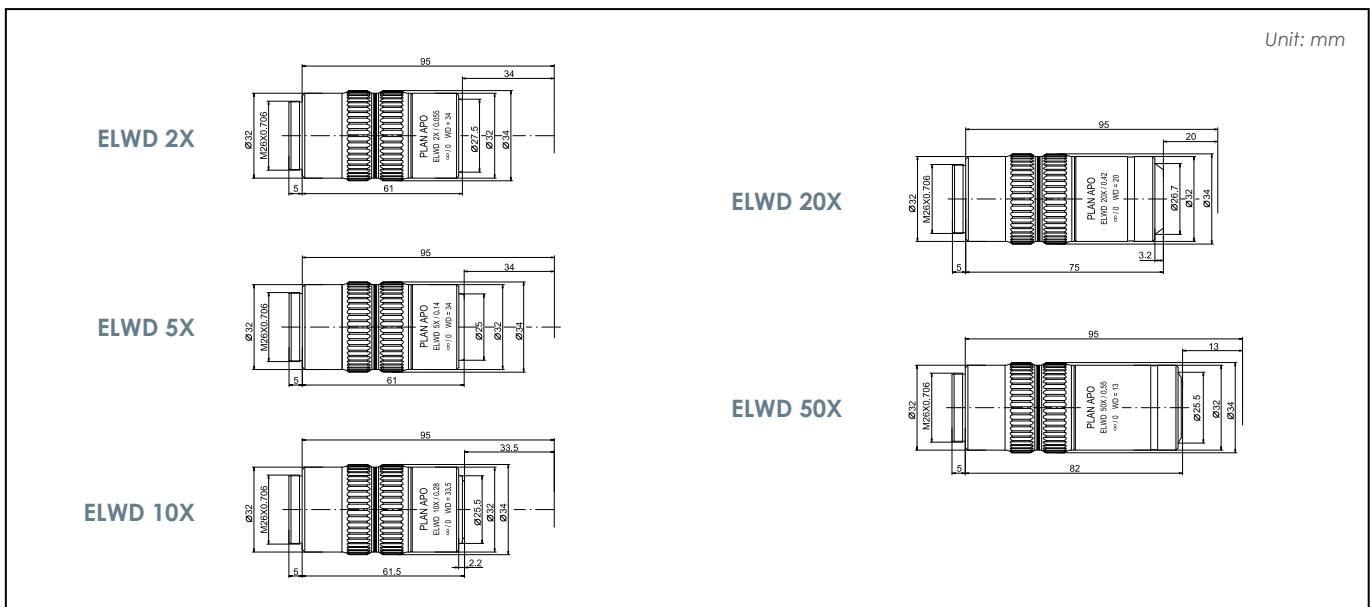
- The infinity corrected and strain-free optical system provides crisp and high contrast images at the numerical apertures and working distance demanded.



ELWD 50X

Standard Objective

Schematic Diagrams of Plan Achromat ELWD Objectives



Specifications Chart Plan Achromat ELWD Objectives

Mag.	N.A	W.D (mm)	F (mm)	R (μm)	D.F (μm)	FOV (mm) (Ø24 eyepiece)	FOV (VxH,mm) (1/2" chip sensor)	FOV (VxH,mm) (2/3" chip sensor)	Weight (g)
ELWD 2X	0.055	34.0	100	5.0	91	Ø12	2.4x3.2	3.3x4.4	250
ELWD 5X	0.140	34.0	40	2.0	14	Ø 4.8	0.96x1.28	1.32x1.76	240
ELWD 10X	0.280	33.5	20	1.0	3.5	Ø 2.4	0.48x0.64	0.66x0.88	250
ELWD 20X	0.420	20.0	10	0.7	1.6	Ø 1.2	0.24x0.32	0.33x0.44	300
ELWD 50X	0.550	13.0	4	0.5	0.9	Ø 0.48	0.192x0.256	0.264x0.352	320

Extra Long Working Distance Objectives

HIGH NUMERICAL APERTURE

PLAN APO ELWD HNA

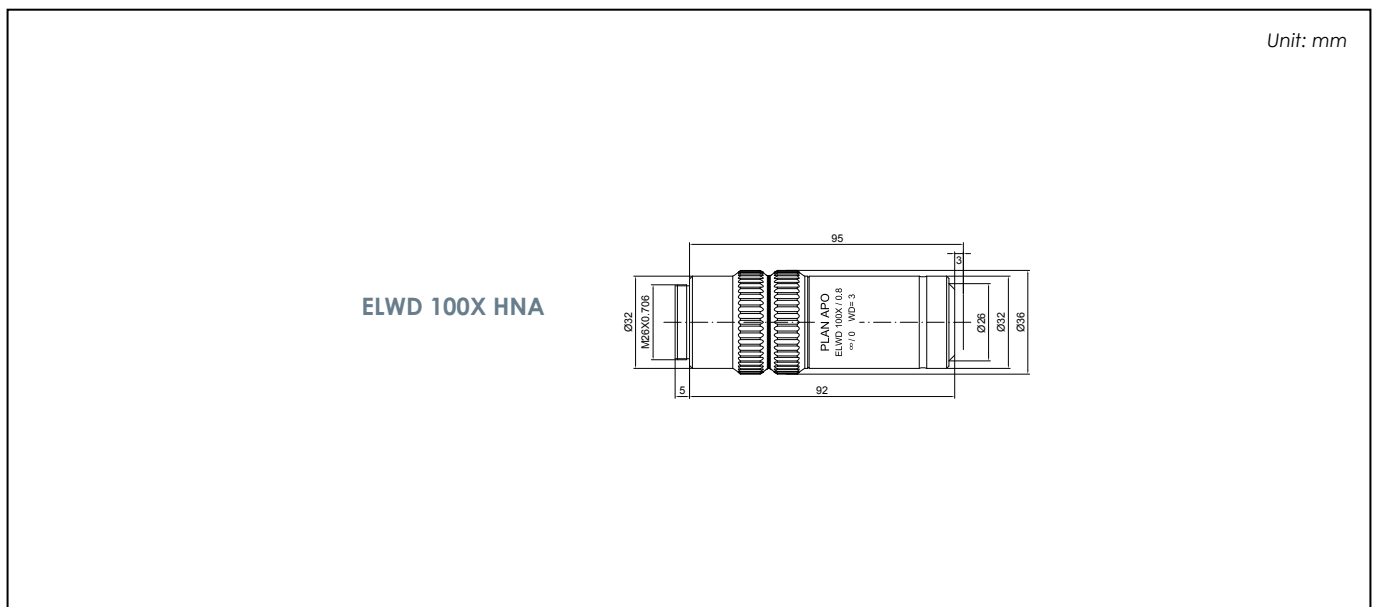
- Constructed for optimum resolution and image clarity, the high numerical aperture extra long Plan Apochromat objective is ideal for applications requiring both working distance and a high numerical aperture.
- The infinity corrected and strain-free optical system provides crisp and high contrast images at the working distance demanded.



ELWD 100X HNA

High Numerical Aperture Objective

Schematic Diagrams of Plan Apochromat ELWD Objective HNA [High Numerical Aperture]



Specifications Chart

Plan Apochromat ELWD Objective HNA [High Numerical Aperture]

Mag.	N.A	W.D (mm)	F (mm)	R (µm)	D.F (µm)	FOV (mm) (Ø24 eyepiece)	FOV (VxH,mm) (1/2" chip sensor)	FOV (VxH,mm) (2/3" chip sensor)	Weight (g)
ELWD 100X HNA	0.800	3.0	2.0	0.34	0.43	Ø 0.24	0.048x0.064	0.066x0.088	450



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Ultra Long Working Distance Objectives

PLAN APO ULWD

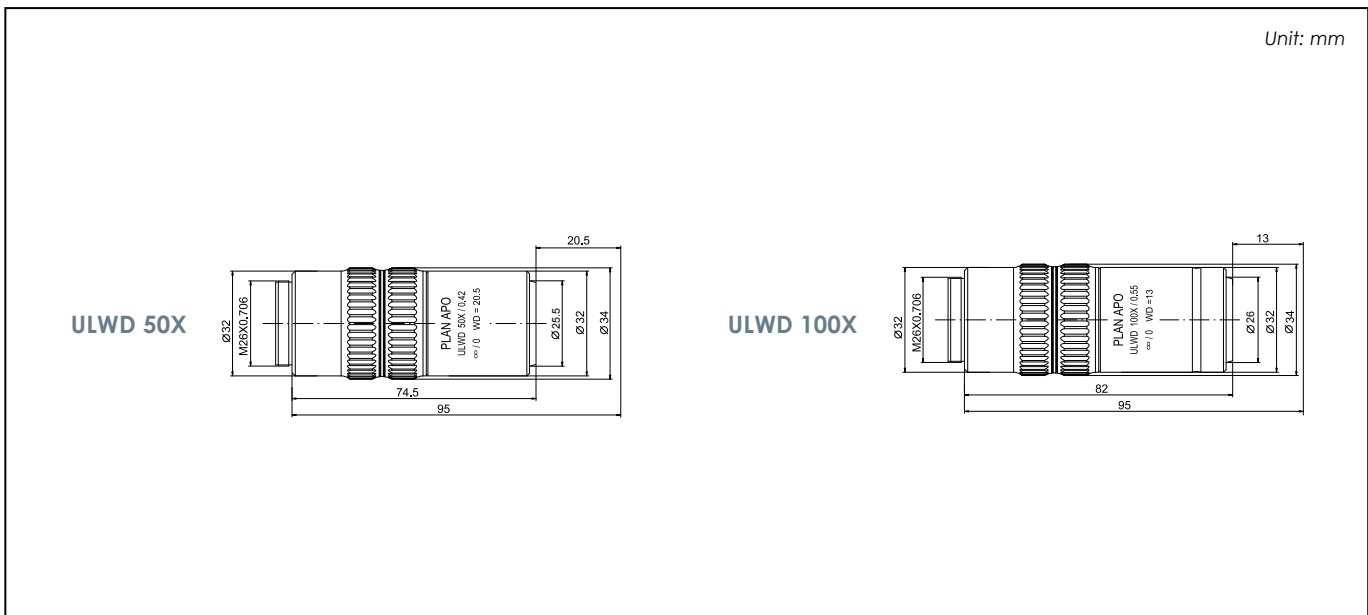
- Corrected within the 24mm field of view for all optical aberrations throughout the visible spectrum, the ultra long Plan Apochromat objectives produce flat and true colour images with the extra amount of working distance demanded.



ULWD 100X

Ultra Long Objective

Schematic Diagrams of Plan Apochromat ULWD Objectives



Specifications Chart Plan Apochromat ULWD Objectives

Mag.	N.A	W.D (mm)	F (mm)	R (µm)	D.F (µm)	FOV (mm) (Ø24 eyepiece)	FOV (VxH,mm) (1/2" chip sensor)	FOV (VxH,mm) (2/3" chip sensor)	Weight (g)
ULWD 50X	0.420	20.5	4	0.7	1.6	Ø 0.48	0.10x0.13	0.132x0.176	300
ULWD 100X	0.550	13.0	2	0.5	0.9	Ø 0.24	0.05x0.06	0.066x0.088	340

Extra Long Working Distance Objectives

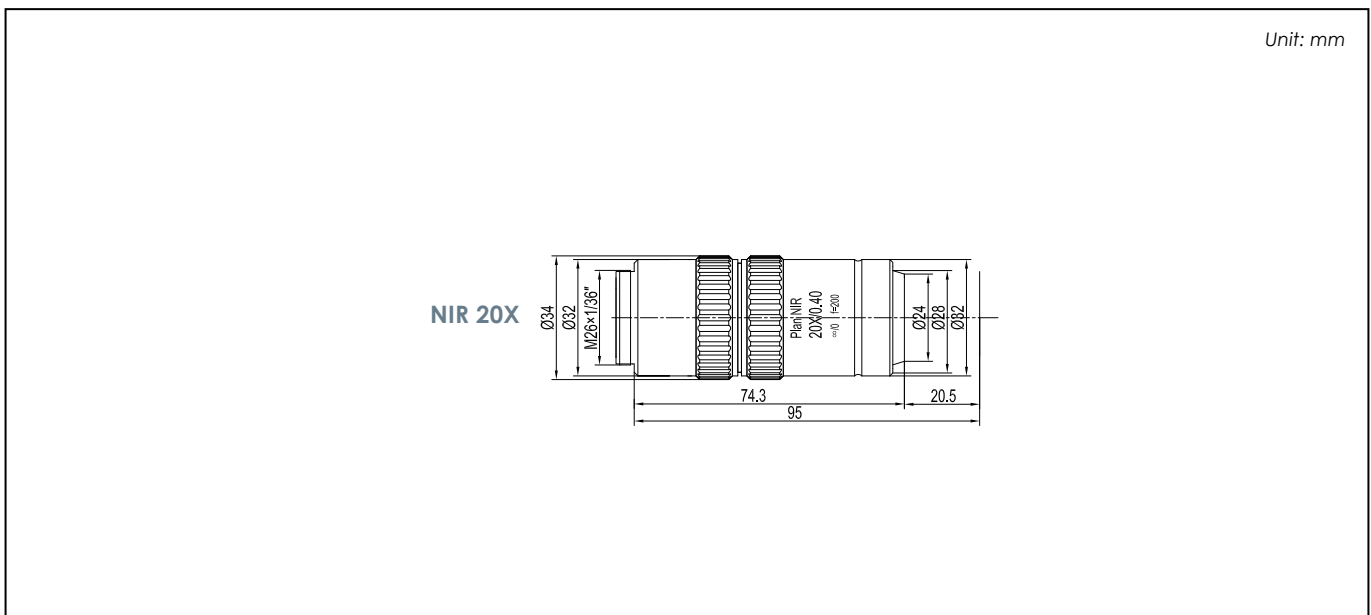
Plan NIR

- The infinity corrected and strain-free optical system provides crisp and high contrast images at the numerical apertures and working distance demanded.
- Designed to focus within the depth of focus, even when the laser wavelength used changes from the visible radiation (wavelength 532nm) to the near-infrared radiation range (wavelength 1064nm).
- Fit a wide range of laser applications, such as laser-cutting fine-films of semiconductors and of liquid crystal substrates and much more.



Plan NIR 20X
NIR Objective

Schematic Diagrams of Plan NIR Objective



Specifications Chart Plan NIR Objective

Mag.	N.A.	W.D. (mm)	F (mm)	R (μ m)	D.F. (μ m)	FOV (mm) (Ø24 eyepiece)	FOV (VxH,mm) (1/2" chip sensor)	FOV (VxH,mm) (2/3" chip sensor)	Weight (g)
NIR 20X	0.4	20.5	10	0.7	1.7	Ø 1.2	0.24x0.32	0.33x0.44	300

Extra Long Working Distance Objectives

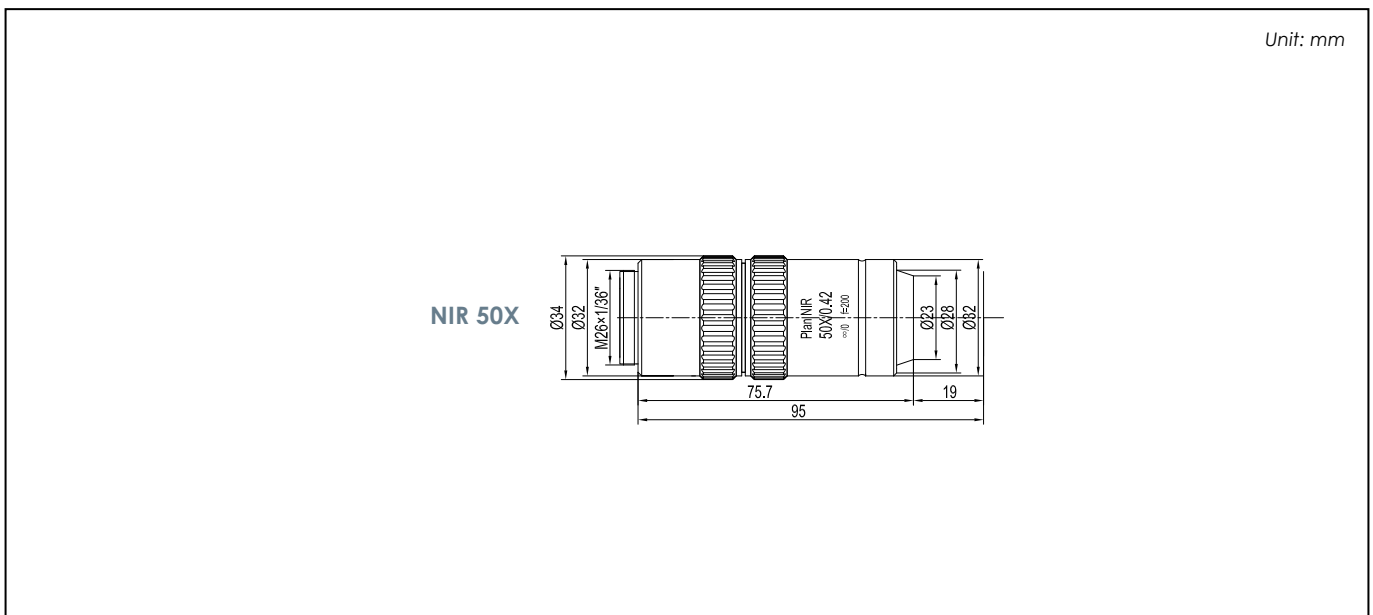
Plan NIR

- The infinity corrected and strain-free optical system provides crisp and high contrast images at the numerical apertures and working distance demanded.
- Designed to focus within the depth of focus, even when the laser wavelength used changes from the visible radiation (wavelength 532nm) to the near-infrared radiation range (wavelength 1064nm).
- Fit a wide range of laser applications, such as laser-cutting fine-films of semiconductors and of liquid crystal substrates and much more.



Plan NIR 50X
NIR Objective

Schematic Diagrams of Plan NIR Objective



Specifications Chart Plan NIR Objective

Mag.	N.A.	W.D. (mm)	F (mm)	R (μm)	D.F. (μm)	FOV (mm) (Ø24 eyepiece)	FOV (VxH,mm) (1/2" chip sensor)	FOV (VxH,mm) (2/3" chip sensor)	Weight (g)
NIR 50X	0.42	19.0	4	0.65	1.6	Ø 0.48	0.096x0.128	0.132x0.176	320

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